

## **Amendments to the Claims:**

*This listing of claims will replace all prior versions, and listings, of claims in the application:*

Claims 1 - 4. (Cancelled)

5. (Previously Presented) A process for removing  $\text{AlCl}_3$  from a compound mixture comprising organochlorosilanes and having an  $\text{AlCl}_3$  content of  $> 200$  ppm based on the weight of organochlorosilanes, comprising diluting the compound mixture with diluent comprising organochlorosilanes or mixtures of chloromethane and organochlorosilanes to form a product stream with  $< 15$  weight percent solids at a simultaneous concentration of  $< 25$  weight percent of components having a boiling point  $> 71^\circ\text{C}$  at 1013 hPa, and separating this product stream in an evaporator unit at a temperature  $< 165^\circ\text{C}$  into volatile compounds and  $\text{AlCl}_3$ -containing solid.

6. (Previously Presented) The process of claim 5, wherein the compound mixture is derived from the direct synthesis of alkylchlorosilanes, or from the  $\text{AlCl}_3$ -catalysed high boiler cleavage of by-products of the direct synthesis.

7. (Currently Amended) The process of claim 5, wherein the organochlorosilanes are alkylchlorosilanes of the formula  $\text{R}_a\text{H}_b\text{SiCl}_{4-a-b}$  in which a is 1, 2, or 3 [[or 4]], b is 0, 1 or 2, [[and]] R is a methyl, ethyl, butyl or propyl radical, and at least one chlorine is present.

8. (Currently Amended) The process of claim 6, wherein the organochlorosilanes are alkylchlorosilanes of the formula  $\text{R}_a\text{H}_b\text{SiCl}_{4-a-b}$  in which a is 1, 2, or 3 [[or 4]], b is 0, 1 or 2, [[and]] R is a methyl, ethyl, butyl or propyl radical, and at least one chlorine is present.

9. (Previously Presented) The process of claim 5, wherein the evaporator unit used is a spray evaporator, thin-layer evaporator, or thin-film evaporator.

10. (Previously Presented) The process of claim 6, wherein the evaporator unit used is a spray evaporator, thin-layer evaporator, or thin-film evaporator.

11. (Previously Presented) The process of claim 8, wherein the evaporator unit used is a spray evaporator, thin-layer evaporator, or thin-film evaporator.